

Interaction of point defects with impurities in the Si-SiO₂ system and its influence on the interface properties

Kropman, Daniel; Mellikov, Enn; Käerner, Tiit; Heinmaa, Ivo; Laas, Tõnu; Londos, Charalampos; Misiuk, Andrzej Solid state phenomena 2011 / p. 263-266 <https://www.sciencedirect.com/science/article/pii/S0040609009014564>

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Stress relaxation mechanism by strain in the Si-SiO₂ system and its influence on the interface properties

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